SVCS plasma reactor system is fully automatic compact table top equipment, custom designed and built for particular research needs. It can be used for broad range of R&D applications including (but not limited to) well known processes as deposition, etching, ashing.

Process media dosing, vacuum and temperature control are independent on each other which provides high degree of process flexibility. Process media selection is broad. Not only gaseous but also liquid/vapour reagents are possible with precise electronic dosing amount control and high performance evaporator. The ultra high purity system design, with electronic mass flow control for both gases and liquids, allows to use also corrosive, flammable or toxic media with no safety risk for research personnel. Plasma RF generators are available with a range of frequencies and power levels, associated tunning circuits for both capacitively and inductively coupled plasma. Chamber pressure is controlled by butterfly control valve or gas ballast system. Control system with touch screen interface allows user to create process recipes with unlimited possibilities to set all process variables.
RF Plasma Multifunction Reactor

Technical Data

- **Chamber size**: cylindrical, 110 mm diameter, 180 mm length
- **Temperature range**: ambient (optionally heated up to 350 °C)
- **Pressure range**: vacuum to atmospheric pressure
- **Process media**: up to 5 ultra-high purity gas lines with electronic mass flow control, 1 liquid reagent with evaporator and precise mass dosing
- **RF frequencies**: 13.56 MHz, optionally 40 and 450 kHz
- **RF power**: 100 W
- **Option**: additional gas and liquid lines in a custom designed enclosure vacuum pumping system

Dimensions are varying with configuration, please consult factory.